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| APPLICATION NO. | FILING DATE | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO. | CONFIRMATION NO. |
|--|-----------------|----------------------|-----------------------------------|------------------|
| 10/659,954 | 09/11/2003 | Myoung-soo Kim | 8836-185 CIP 5871 (IB12070-US- | |
| 22150 | 7590 02/17/2005 | | EXAM | INER |
| F. CHAU & ASSOCIATES, LLC 130 WOODBURY ROAD | | | LE, THAO P | |
| | Y, NY 11797 | | ART UNIT | PAPER NUMBER |
| · | | | 2818 | |
| | | | DATE MAILED: 02/17/200 | 5 |

Please find below and/or attached an Office communication concerning this application or proceeding.

| <i>.</i> | Application No. | Applicant(s) | | | | |
|---|---|---|--|--|--|--|
| | 10/659,954 | KIM, MYOUNG-SOO | | | | |
| Office Action Summary | Examiner | Art Unit | | | | |
| | Thao P. Le | 2818 | | | | |
| The MAILING DATE of this communication app Period for Reply | ears on the cover sheet with the c | orrespondence address | | | | |
| A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b). | within the statutory minimum of thirty (30) days a reply and will expire SIX (6) MONTHS from the cause the application to become ABANDONE | s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133). | | | | |
| Status | | | | | | |
| 1) Responsive to communication(s) filed on 13 De | ecember 2004. | | | | | |
| 2a) ☐ This action is FINAL . 2b) ☑ This | This action is FINAL. 2b)⊠ This action is non-final. | | | | | |
| . — | Since this application is in condition for allowance except for formal matters, prosecution as to the merits is | | | | | |
| closed in accordance with the practice under E | x parte Quayle, 1935 C.D. 11, 45 | 3 O.G. 213. | | | | |
| Disposition of Claims | | | | | | |
| 4) Claim(s) 14-24 is/are pending in the application 4a) Of the above claim(s) is/are withdraw 5) Claim(s) is/are allowed. 6) Claim(s) 14-24 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or | vn from consideration. | | | | | |
| Application Papers | • | | | | | |
| 9) ☐ The specification is objected to by the Examine 10) ☑ The drawing(s) filed on 9/11/03 is/are: a) ☑ accomplicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) ☐ The oath or declaration is objected to by the Examine 10. | cepted or b) objected to by the drawing(s) be held in abeyance. See ion is required if the drawing(s) is obj | e 37 CFR 1.85(a). ected to. See 37 CFR 1.121(d). | | | | |
| Priority under 35 U.S.C. § 119 | | - | | | | |
| 12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau * See the attached detailed Office action for a list | s have been received. s have been received in Application ity documents have been received i (PCT Rule 17.2(a)). | on No ed in this National Stage | | | | |
| Attachment(s) | | | | | | |
| Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date | 4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other: | • | | | | |

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DETAILED ACTION

- Examiner took notice of remarks and amendments made on 12/13/2004.
 Claims 1-13 have been cancelled.
- 2. Claims 14-24 are pending in this application.
- 3. Examiner withdrew the previous double patenting that applied for claims 14-24.

Claim Rejections - 35 USC § 102

4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.
- 5. Claims 14-15 are rejected under 35 USC 102 (a) as being anticipated by Ando, U.S. Patent No. 6,475,862.

Regarding claim 14, Ando discloses a method of forming a semiconductor device comprising (See Figs. 5-10 and Cols. 1-14): forming isolation layers to define a first region, second region, and third region (Figs. 5A, 6A, 7A), forming a first gate insulating layer and first gate conductive pattern stacked sequentially on the first region, second region, and third region and patterning the first gate conductive pattern and second gate conductive pattern to form a first gate, second gate, and third gate (Col. 9), wherein the

first gate insulating layer (2.0 nm), the second gate insulating layer (2.5 nm), and the third gate insulating layer (5.0 nm) having varying thicknesses and each layer has a different thickness than the other layers (Figs. 5J, 6J, 7J).

Regarding claim 15, Ando discloses the limitations disclosed in claim 15, forming a first gate insulating layer and conductive layer on the first region, forming a second gate conductive layer on the second and third gate insulating regions, patterning the second gate conductive layer to form second conductive pattern.

Claim Rejections - 35 USC § 103

- 6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 7. Claims 16-24 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ando, U.S. Patent No. 6,475,862.

Regarding claims 16-23, Ando fails to disclose the formation of dielectric between lower electrode and upper electrode, it would have been obvious to one having

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ordinary skill in the art of forming capacitors that a dielectric layer such as silicon oxide, silicon nitride is required between lower electrode and upper electrode in any capacitors.

Regarding to claim 24, Ando discloses the thicknesses of the first insulating layer, the second insulating layer, and the third insulating layer which fall into the ranged as cited in claim 24 (convert from nm to Angstrom).

8. A shortened statutory period for response to this action is set to expire 3 (three) months and 0 (zero) day from the day of this letter. Failure to respond within the period for response will cause the application to become abandoned (see M.P.E.P 710.02(b)).

Conclusion

9. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thao P. Le whose telephone number is 571-272-1785. The examiner can normally be reached on M-T (7-6).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Nelms can be reached on 571-272-1787. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Thao P. Le Examiner

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